



Advanced Readout CMOS Architectures with Depleted Integrated sensor Arrays

ARCADIA FD-MAPS: simulation, characterization and perspectives for high resolution timing applications

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n-epi

n-sub

on behalf of the ARCADIA collaboration

deep pwell

Goals and status of the ARCADIA project

Main objective

Development of large (1.2×1.2) cm² demonstrator chip of 512×512 fully depleted monolithic pixels with 25μ m pitch.

Targeted applications

- future high energy experiments
- space applications \bullet
- medical and industrial scanners

Specifications



ARCADIA sensor concept

- Fully depleted substrate with low front bias \rightarrow charge collection via drift
- n-in-n device •
- pn-junction on backside
- depletion voltage applied through backside, only low bias voltage from top
- low-resistive epi layer delays the onset punchthrough currents
- backside processing (diode + GR) for thick sensors (> 100μ m)

- low power consumption 5-20mW/cm²
- hit rates up to 10-100MHz/cm²
- scalable matrix size up to 24cm²
- radiation tolerance 10-100krad / 10¹¹-10¹² neq/cm²
- full signal processing within 1-10µs

Timeline & Production

		wafers	d _{Si} [µm]
1st run delivered	June 2021	12	50/100/200
2nd run delivered	March 2022	11	50/100
3rd run – final layout	June 2022	12	50//200
3rd run predicted arrival	end 2022		



ARCADIA 1st run 8" wafer



Concept first realized in SEED project

Main Demonstrator (MD) chip

- matrix core 512 \times 512 pixels of 25 μ m pitch
- pixels are \sim (50/50)% analogue/digital
- 2 types of front-ends
- sensor diode about 20% of total area
- clock-less matrix (to minimize power dissipation)
- global shutter with serial readout
- output fully digital



Results of 1st Engineering run

Main Demonstrator functional

- DAQ up and running
- Debugging ongoing (sources of additional leakage currents found and eliminated)
- first tests of a MD1 (200 μ m thickness) with sources and cosmic rays



P. Giubiliano Uni Padova



Matching of TCAD simulations

- IV/CV measurements from 4 positions of each wafer
- TCAD input parameters (substrate doping, epilayer thickness, total thickness) varied within uncertainty given by foundry
- Found excellent agreement with the IV measurements, and depletion V_{dpl} and punchthough voltages V_{pt}
- Parameters matched for each wafer type individually









Further tests with more chips **ongoing**

Variety of passive pixel matrices

- Tests of pixels with $(10/25/50)\mu m$ pitch from different wafers in different thicknesses
- Tests with different designs of pixels of same pitch
- Radiation study with X-rays from 10krad to 10Mrad

 \rightarrow results will be presented at iWORID 2022

Microscopic picture of two 1×1 mm² passive matrices with pixels of 50 and 25μ m pitch



T. Corradino, Uni Trento

TCAD, $V_{bot} = -22V$

TCAD, $V_{bot} = -26V$ --- TCAD, $V_{bot} = -30V$

Capacitance measurements

- Depletion voltage varied from -20 to -25V
- At operating point of $V_{ptop} = 0.8V$ the single pixel capacitance found < 5fF



- Tested different pixel geometries, optimised in simulation for low capacitance or fast charge collection
- Trends found in simulation (including oxide charges), confirmed in data
- $50\mu m$ pixel with < 5 fF

TCT measurements

Allpix² simulations

200MeV µ⁻

50⊢d_{si}=50µm

60

- Focused IR laser, 1GHz bandwidth oscilloscope on $(500 \times 500) \mu m^2 pad$
- Strong impact of 1GHz oscilloscope, which can be well reproduced in simulation with digital low pass filter
- TCAD simulation based on matched parameters per wafer

95% charge collection in: • < 1.4ns in d_{si} =50µm

Torin

Polite

Andrini, Ferrero,

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Summary

- Successful 2 production runs, w/ and w/o backside processing in n-type and p-type (with 50µm n-type epitaxial substrate) wafers
- Passive pixel matrices used for characterization of different pixel layouts, and to study impact of oxide charges
- Successful reproduction of operating voltages in TCAD within the process uncertainties
- Single pixel capacitances of MD1 ($25\mu m$ pitch) < 5fF
- First particles seen by MD1
- Design of specialized timing chip completed, integrating pad-like pixels with expected

< 5ns in d_{si}=100 μ m

- Pad-like MAPs in 50 μ m pitch for chip optimised for timing implemented in 2nd run
- \rightarrow first results will be presented at IEEE NSS 2022 Time resolution at different CFD

50µm pitch

100µm pitch

150µm pitch

200µm pitch



Intrinsic timing resolution in Allpix² simulations for MIPs

< 20ps for constrant fractions < 40% for pixel pitches > 100μ m in d_{si}= 50μ m

95% charge collection in 1.4ns

Outlook and plans – 3rd run

• Design of new test-structures ongoing: gated diodes on front side for oxide charge concentration measurements, diodes for epi-layer doping profiles, and *new large pixels* including a charge multiplication layer

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